Applicant:

Jurgensen et al.

18:05 FROM:LSI Logic

Group Art Unit:

Serial No.:

Filed:

Attorney Docket No:

98-058/ID

For:

Confinement Device for Use in Dry

Etching of Substrate Surface and Method of Dry Etching a Wafer

Surface

PRELIMINARY AMENDMENT

Hon. Commissioner of Patents and Trademarks Washington, D.C. 20231

Dear Sir:

Prior to examination, please amend the application as follows:

IN THE CLAIMS

Please cancel claims 1-21.